

1	15	Hits	Search Text	DBs	Time Stamp
2	4	517 and 513		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:49	
3	20	523 and 513		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:48	
4	5921	257/296.ccls		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:48	
5	62	(pad adj oxide) with thickness with engetroma with (silicon adj oxide)		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:48	
6	0	538 and 537 and @pd>"20050105"		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:49	
7	96	(conductive adj layer) with "TiN" with capacitor		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:48	
8	2	540 and 537 and @pd>"20050105"		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:48	
9	45	recesses and (hard adj mask adj layer) and conformal and capacitor		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
10	35	52 and 53 and 54		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
11	45	recesses and (hard adj mask adj layer) and conformal and capacitor		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
12	18	recesses and (hard adj mask adj layer) and conformal and capacitor and (bottom adj electrode)		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
13	1	capacitor and (bottom adj electrode) and (top adj electrode) and bottle and shallow		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
14	5	(capacitor with top with electrode) same (sidewall adj spacer) same (hard adj mask)		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
15	5	recesses and (hard adj mask adj layer) and conformal and capacitor and @pd>"20050105"		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
16	13994	shallow adj trench adj isolation		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
17	3209	257/296.ccls.		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
18	8115	pad adj oxide		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
19	8	529 and 530 and 531 and @pd>"20050105"		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
20	5	recesses and (hard adj mask adj layer) and conformal and capacitor and @pd>"20050105"		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
21	1	recesses and (hard adj mask adj layer) and conformal and capacitor and (bottom adj electrode) and @pd>"20050105"		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
22	0	capacitor and (bottom adj electrode) and (top adj electrode) and bottle and shallow and @pd>"20050105"		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
23	0	(capacitor with top with electrode) same (sidewall adj spacer) same (hard adj mask) and @pd>"20050105"		US-PGFUB; USPAT; 2005/05/10 EPO; JPO; DERMENT; 15:47	
24	10	("6256248" "6468855" "4713678" "6420226" "6580110").pn.		US-PGFUB; USPAT; 2005/01/06 EPO; JPO; DERMENT; 13:19	
25	2	("6256248" "6468855" "4713678" "6420226" "6580110").pn. and ONO		US-PGFUB; USPAT; 2005/01/06 EPO; JPO; DERMENT; 13:19	
26	2	"20040036051".pn.		US-PGFUB; USPAT; 2005/01/06 EPO; JPO; DERMENT; 12:56	
27	5626	(conductive adj layer) with "TiN"		US-PGFUB; USPAT; 2005/01/05 EPO; JPO; DERMENT; 15:26	

updated EAST 5/10/2005